TM01

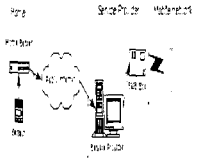
Poster Session

09:00 – 11:00 **Chair1 : Jinyoung Kim (Tongmyong Univ., Korea)**
Room : Base 2nd Floor-Zillertal **Chair2 :**

TM01-13

An automatic Notification Service Using the OSGi Service Platform and SMS module

Kyu-Chang Kang, Dong-Oh Kang, Jeon-Woo Lee(ETRI, KOREA)



In the era of home automation, we need more context-aware and intelligent service applications than before. For these applications, a service gateway as a platform is required to bridge the gap between external data networks to internal home networks. Also, the service gateway enables customers to receive new classes of home services. The OSGi service platform is a good solution for the service gateway since it can deliver new applications dynamically from a broader network. In the near future, every home will be equipped with a residential gateway powered by the OSGi, and will demand value-added service applications, such as home security monitoring and safety alerts. In this pa...

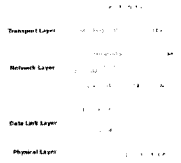
Keyword : OSGi, Remote Monitoring, SMS

TM01-14

A modified TCP/IP over IEEE-1394 for real-time control communication

Bokjin Youm , Jaehyun Park(Inha Univ., KOREA)

- Introduction
- TCP/IP over IEEE1394
- Modified TCP/IP
- Implementation and Evaluation
- Conclusions

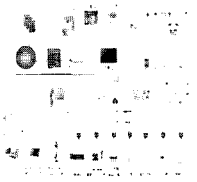


TM01-15

A Case Study on an Internet-based Home Automation Control

Young-Jo Cho, Hyo-Sup Kim, GuhnSong Lee(IControls Inc., KOREA)

1. Introduction
2. Trends in Home Automation
3. Elementary Technologies
4. Fuctional Requirements
5. A Design of Network-based Home Automation System
6. Concluding Remark



TM01-16

A Control Algorithm for Wafer Edge Exposure Process

Hong Lae Park(BLUEcord Tech., KOREA), Joon Lyou(Chungnam Nat'l Univ., KOREA)

In the semiconductor fabrication, particle contamination is wide-spread and one of major causes to yield loss. Extensive testing has revealed that even careful handling of wafers during processing may cause photo-resist materials to flake off wafer edges. So, to remove the photo-resist at the outer 5mm of wafers, UV(UltraViolet) rays are exposed. WEE (Wafer Edge Exposure) process station is the system that exposes the wafer edge as prespecified by controlling the positioning mechanism and maintaining the light intensity level
In this work, WEE process station has been designed so as to significantly lower the amount of particle contamination which occurs even during the most r...

TM01-17

Robot Off-line Programming Based on CAD Data in Adhesive Application System for Shoe Outsoles and Uppers

Jinyoung Kim Jinyoung Kim , Dongjoong Kang(Tongmyong Information Univ., KOREA), Hyungsuck Cho(KAIST, KOREA), Taejung Lho, Hyungkeun Ahn(Tongmyong Information Univ., KOREA)

abstract
chapter 1-6
references

TM01-18

Tool Planning in Assembly Simulation and its Application

Huafei Liao, Linxuan Zhang(Tsinghua Univ., CHINA)

Huafei Liao is a graduate student of the Automation department in Tsinghua University, China. His research involves computer-aided process planning, 3D CAD/CAM, virtual reality, and feature recognition.